O P ESAN 10/786726

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Leonard Forbes

Examiner:

Unknown

rial No.:

10/786,726

Group Art Unit:

Unknown 303.680US3

Filed: Title: February 25, 2004 Docket: 3 STATIC NVRAM WITH ULTRA THIN TUNNEL OXIDES

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 *et. seq.*, the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicant respectfully requests that this Supplemental Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicant with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Supplemental Information Disclosure Statement. However, if an Office Action on the merits has been mailed, the Commissioner is hereby authorized to charge the required fees to Deposit Account No. 19-0743 in order to have this Supplemental Information Disclosure Statement considered.

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The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

The present application is either a U.S. national patent application filed after June 30, 2003 or an international application that entered the national stage under 35 U.S.C. § 371 after June 30, 2003. Thus, Applicant believes that the U.S. Patent & Trademark Office has waived the requirement under 37 C.F.R. 1.98 (a)(2)(i) for submitting a copy of each cited U.S. patent and each U.S. patent application publication. The waiver is provided in a pre-OG notice from the U.S. Patent & Trademark Office entitled "Information Disclosure Statements May Be Filed Without Copies of U.S. Patents and Published Applications in Patent Applications filed after June 30, 2003" and dated July 11, 2003. Applicant acknowledges the requirement to submit copies of foreign patent documents and non-patent literature in accordance with 37 C.F.R. 1.98(a)(2).

Respectfully submitted,

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By his Representatives,

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PTC/SB/08A(10-01)
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Ident the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Substine for form 1449APTO SURE STATE WEADON APPLICANT Complete if Known 10/786726 **Application Number** February 25, 2004 (Use as many sheets as necessary) Filing Date **First Named Inventor** Forbes, Leonard **Group Art Unit** Unknown Unknown **Examiner Name** Attorney Docket No: 303.680US3 Sheet 1 of 3

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

DW

Applicant: Lanard Forbes

Title TRADE TATIC NVRAM WITH ULTRA THIN TUNNEL OXIDES

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Serial No.: 10/786,726

Filed:

February 25, 2004

Due Date: N/A

Examiner:

Unknown

Group Art Unit: Unknown

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

We are transmitting herewith the following attached items (as indicated with an "X"):

 \underline{X} A return postcard.

X A Supplemental Information Disclosure Statement (2 pgs.), Form 1449 (3 pgs.), and copies of 22 cited documents.

If not provided for in a separate paper filed herewith, Please consider this a PETITION FOR EXTENSION OF TIME for sufficient number of months to enter these papers and please charge any additional fees or credit overpayment to Deposit Account No. 19-0743.

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

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MEREDITH MESCHER

Name

Signature

SCHWEGMAN, LUNDBERG, WOESSNER & KLUTH, P.A.

(GENERAL)